

AMENDMENTS TO THE CLAIMS

1. (Currently amended) A method of manufacturing a plasma display panel,  
wherein:

a structure of the plasma display panel is formed with photolithography; ~~and wherein~~  
at least one of a display electrode, a black layer, an address electrode or a partition wall  
of the structures of the plasma display panel, in a process of forming the structure, is exposed  
using a plurality of photomasks with a same pattern and a different aperture width of an exposure  
part, with a different amount of exposure, an exposure amount radiated from the light source  
when the exposure is made by a photomask with a longer aperture width is larger than an  
exposure amount radiated from the light source when the exposure is made by a photomask with  
a shorter aperture width, wherein the exposure amount is determined by exposure intensity or  
exposure time; and

a portion of the at least one of the display electrode, the black layer, the address electrode  
or the partition wall exposed by the photomask with the longer aperture width is also exposed by  
the photomask with the shorter aperture width.

2. (Currently amended) A method of manufacturing a plasma display panel,  
wherein:

a stripe structure of the plasma display panel is formed with photolithography; ~~wherein~~  
an exposure process of forming at least one of a display ~~[[a]]~~ electrode, a black layer,  
~~[[a]]~~ an address electrode or a partition wall in structures of the plasma display panel, in a  
process of forming the structure, is processed twice using a photomask~~[[,]]~~ and ~~wherein~~ a first

exposure amount and a second exposure amount [[is]] are different, wherein the exposure amount is determined by exposure intensity or exposure time, and

a portion of the at least one of the display electrode, the black layer, the address electrode or the partition wall exposed with the first exposure amount is also exposed with the second exposure amount.

3. (Original) A method of manufacturing a plasma display panel as claimed in claim 2, wherein a larger amount of exposure is approximately two thirds of a total amount of exposure required.

4. (Cancelled)

5. (Previously presented) A method of manufacturing the plasma display panel as claimed in claim 2, wherein either the first exposure amount or the second exposure amount is approximately two thirds of a total amount of exposure required.

6. (Previously presented) A method of manufacturing the plasma display panel as claimed in claim 1, wherein at least one of the structure, immediately after the exposure, a progress speed of a cross-linking reaction is different between at an edge part and a central part of the pattern shape, and the central part proceeds the edge part.

7. (Previously presented) A method of manufacturing the plasma display panel as claimed in claim 2, wherein at least one of the structure, immediately after the exposure, a

progress speed of a cross-linking reaction is different between at an edge part and a central part of the pattern shape, and the central part proceeds the edge part.

8. (Previously presented) A method of manufacturing the plasma display panel as claimed in claim 1, wherein the exposure process is a process for forming an address electrode, and the exposure is made to a photosensitive Ag paste film.

9. (Previously presented) A method of manufacturing the plasma display panel as claimed in claim 2, wherein the exposure process is a process for forming an address electrode, and the exposure is made to a photosensitive Ag paste film.

10. (Previously presented) A method of manufacturing the plasma display panel as claimed in claim 1, wherein the exposure amount is determined by controlling the exposure intensity.

11. (Previously presented) A method of manufacturing the plasma display panel as claimed in claim 1, wherein the exposure amount is determined by controlling the exposure time.

12. (Previously presented) A method of manufacturing the plasma display panel as claimed in claim 2, wherein the exposure amount is determined by controlling the exposure intensity.

13. (Previously presented) A method of manufacturing the plasma display panel as claimed in claim 2, wherein the exposure amount is determined by controlling the exposure time.

14. (Previously presented) A method of manufacturing the plasma display panel as claimed in claim 1, wherein the exposure amount is determined by controlling the exposure intensity or exposure time.

15. (Previously presented) A method of manufacturing the plasma display panel as claimed in claim 2, wherein the exposure amount is determined by controlling the exposure intensity or exposure time.

16. (Previously presented) A method of manufacturing the plasma display panel as claimed in claim 1, wherein the exposure amount radiated from the light source when the exposure is made by the photomask with the longer aperture width is two thirds of a total amount of exposure required.

17. (Previously presented) A method of manufacturing the plasma display panel as claimed in claim 1, wherein the exposure amount radiated from the light source when the exposure is made by the photomask with the shorter aperture width is one third of a total amount of exposure required.

18. (Previously presented) A method of manufacturing the plasma display panel as claimed in claim 2, wherein the first exposure is two thirds of a total amount of exposure required and the second exposure is one third of the exposure amount required.